

REMARKS

Claims 7-23, 50-61 and new claims 63 and 64 are pending in this application. Claim 62 has been cancelled.

The undersigned would like to thank the Examiner for conducting a personal interview on Friday, Apr. 1, 2005. The Examiner and Applicant's representative discussed the cited art, the specification, and the relationship of the cited art to the claims. The Applicants previous arguments, that the cited art does not disclose a slurry comprising first and second oxidizers and exhibiting a synergistically increased metal polishing rate were presented by the Examiner's representative, and are incorporated herein by reference to the Applicant's previous Amendment dated Oct. 14, 2004.

Claim 7 has been amended as was suggested by the Examiner during the interview of Apr. 1, 2005, to recite Markush groups listing the first and second oxidizer species, respectively. Applicants also added a clause that the first and second oxidizers were different species and the second oxidizer not merely a reaction product of the first oxidizer. Applicants respectfully request reconsideration and removal of the rejection to claim 7 and to claims 8-23 and 50-61 depending therefrom in light of this amendment.

New claim 63 presents previously submitted claim 10 in independent form. During the interview of Apr. 1, 2005, Applicant's representative specifically pointed out to the Examiner that while the cited references suggest including a surfactant such that particles repel one another (as recited in dependent claim 9, for example), no reference taught or suggested the inclusion in a slurry a polyelectrolyte in an amount sufficient to encourage the abrasive particles to repel the surface to be polished. While Applicant's representative had argued the independent patentability of this claim during the interview of Apr. 1, 2005, Applicants in new claim 63 have elected to include a Markush group directed toward the first oxidizer (as suggested by the Examiner), as well as the recitation that the first and second oxidizers were different species and the second oxidizer was not merely a reaction product of the first oxidizer.

New claim 64 is presents previously submitted independent claim 7, amended to include a Markush group directed toward the first oxidizer (as suggested by the Examiner), as well as the recitation that the first and second oxidizers were different species and the second oxidizer was not merely a reaction product of the first oxidizer. During the interview of Apr. 1, 2005, Applicants argued the patentability of independent claim 7, showing that the cited art did not

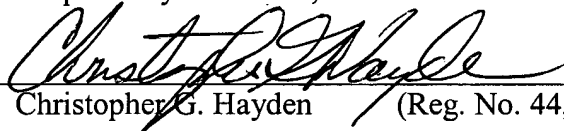
teach a slurry having first and second oxidizers and a synergistically increased polishing rates. The Examiner asked the Applicant's representative to point out the specific passage in the specification that supported the claim to synergistically increased polishing rate. While Applicant's representative was not able to find the specific passages at that time, Applicants would like to direct the Examiner's attention to the text of the specification on for example the first full paragraph on page 21 of the specification, which states: "In accordance with a further aspect of this invention, another unique idea is to blend two different chemistries to achieve synergistic interactions." See also the same text repeated on the last paragraph of that same page. The Examiner noted during the interview of Apr. 1, 2005 that the synergy between oxidizers was shown in the Examples, but the examples all showed only polishing tungsten. Therefore, Applicants' now present new claim 64 that recites the limitations of independent claim 7, amended to include a Markush group directed toward the first oxidizer (as suggested by the Examiner), as well as the recitation that the first and second oxidizers were different species and the second oxidizer was not merely a reaction product of the first oxidizer, AND ALSO that the polishing is limited to polishing a tungsten substrate.

Applicants respectfully request reconsideration and allowance of these claims.

There are no fees believed due in this matter; however, should any fees or credits be deemed necessary, the Examiner is authorized to charge Morgan, Lewis & Bockius LLP Deposit Account No. 50-0310.

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due date)

Respectfully submitted,


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